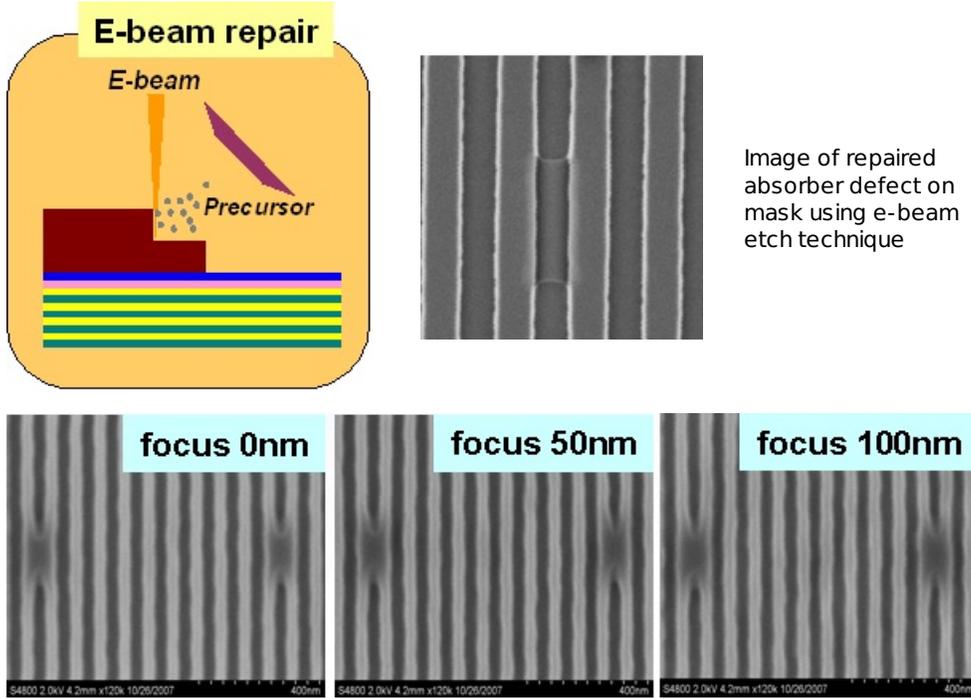


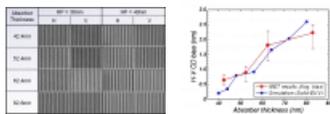
# Mask Development

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The SEMATECH Berkeley MET is used for the testing of mask repair methods. Masks have been repaired using E-beam etching, then used to print through-focus images in resists, demonstrating the effectiveness of the repair.



The SEMATECH Berkeley MET has also been used to verify mask shadowing models: **(Select an image to view full size)**



## References

1. Gi-Sung Yoon et al., 2007 International EUVL Symposium, 28-31 October 2007, Sapporo, Japan
2. Hwan-Seok Seo et al. EIPBN 2008